

FIG. 1
PRIOR ART

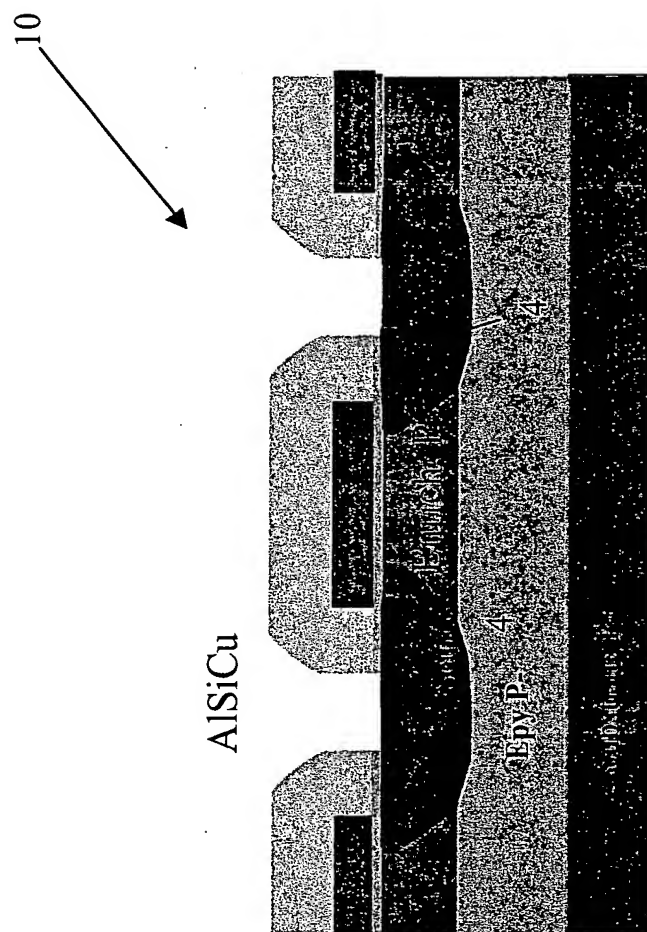


FIG. 2
PRIOR ART

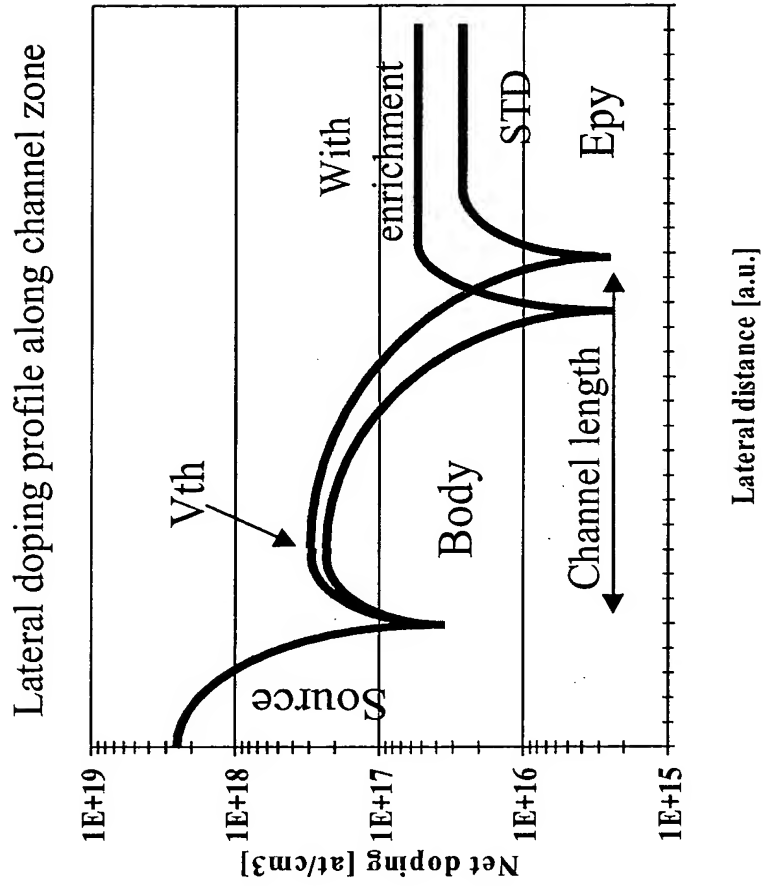
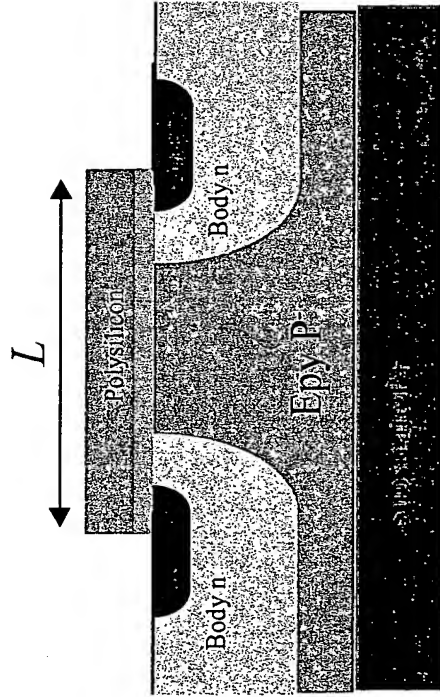


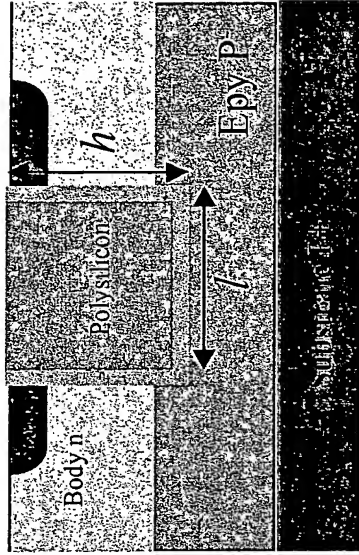
FIG. 3

STD




Gate area $\propto L$

Trench



Gate area $\propto (l+2h)$

FIG. 4

1 

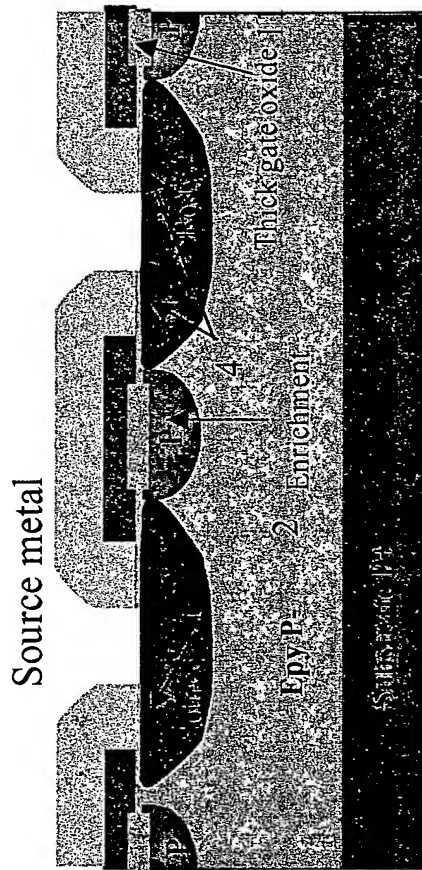


FIG. 5

Enrichment implant

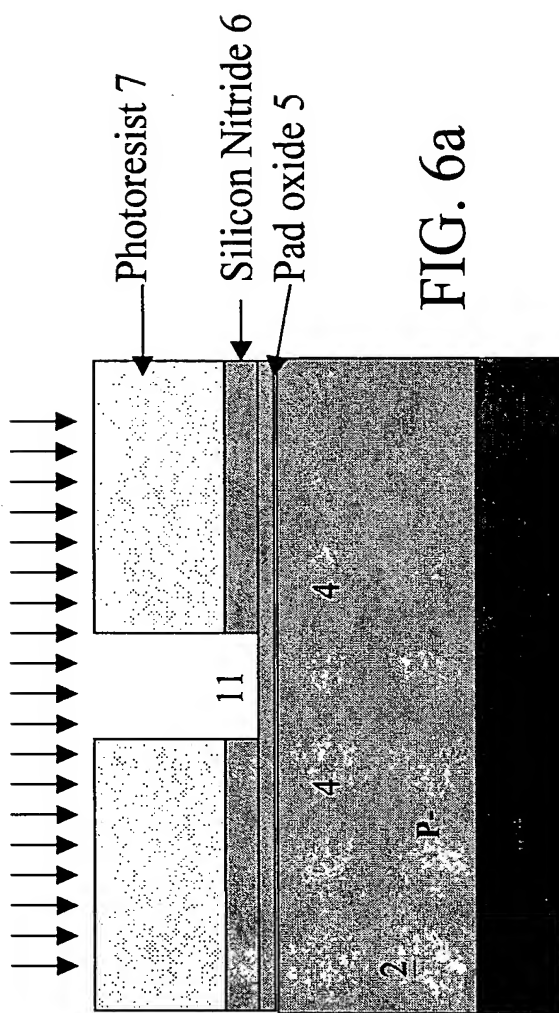


FIG. 6a

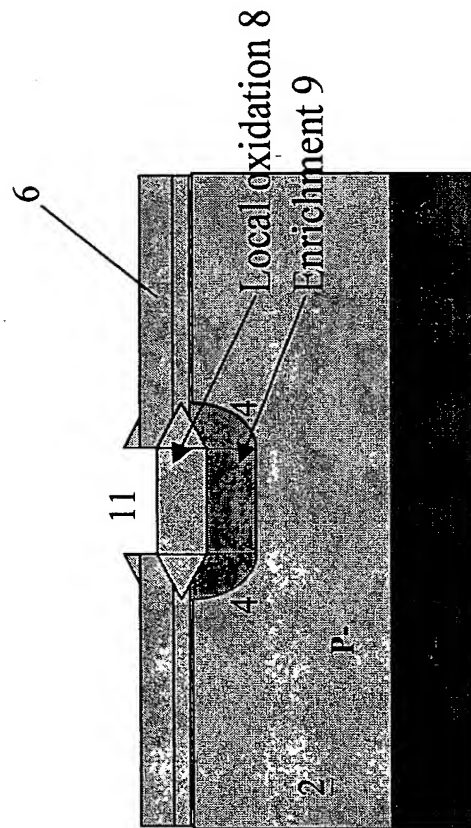


FIG. 6b

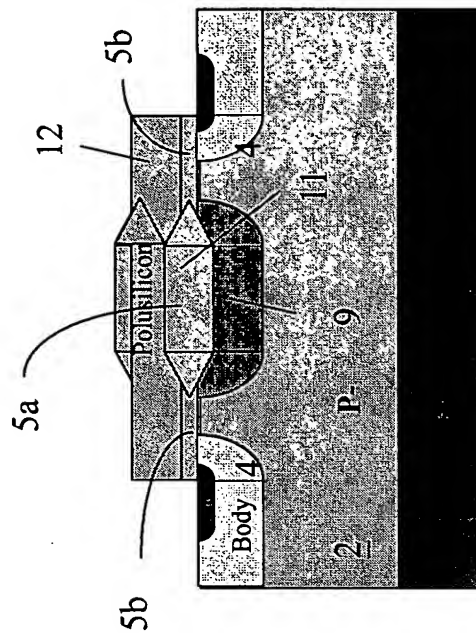


FIG. 6c

Enrichment implant

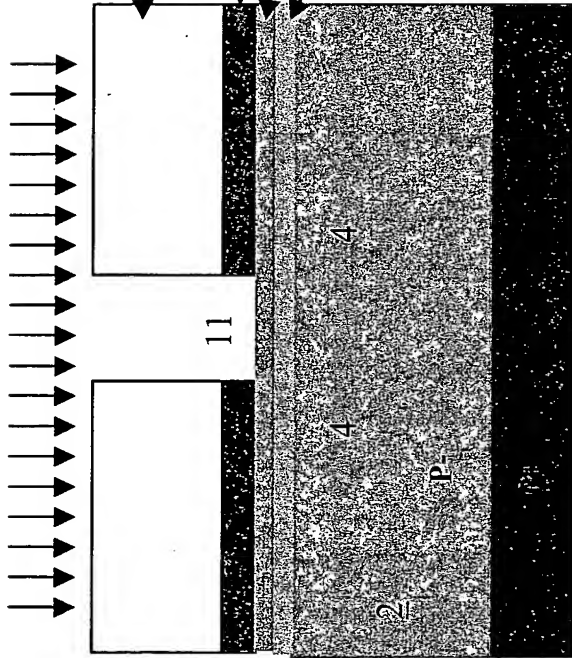


FIG. 7a

Photoresist 7
Silicon Nitride 6
Polysilicon 13
Gate oxide 5

7/8

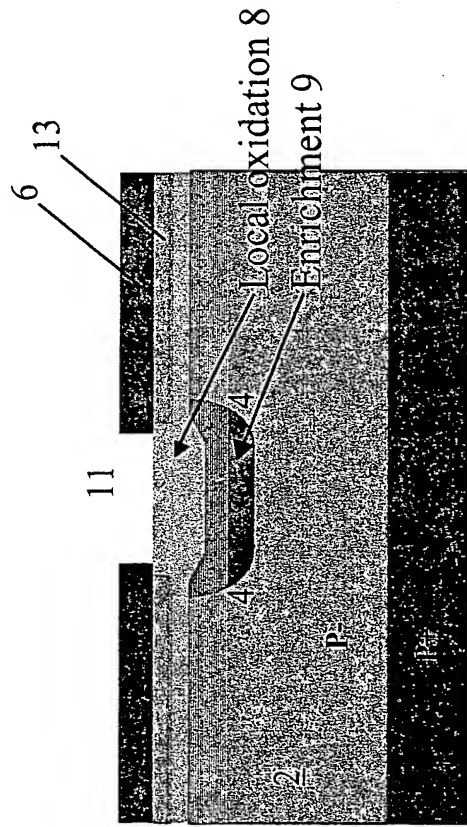


FIG. 7b

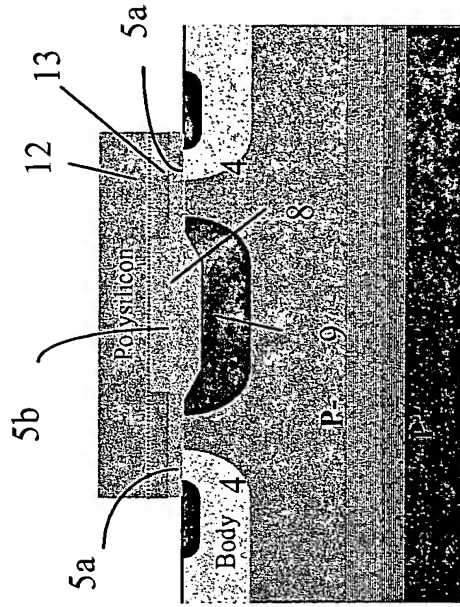


FIG. 7c

BEST AVAILABLE COPY

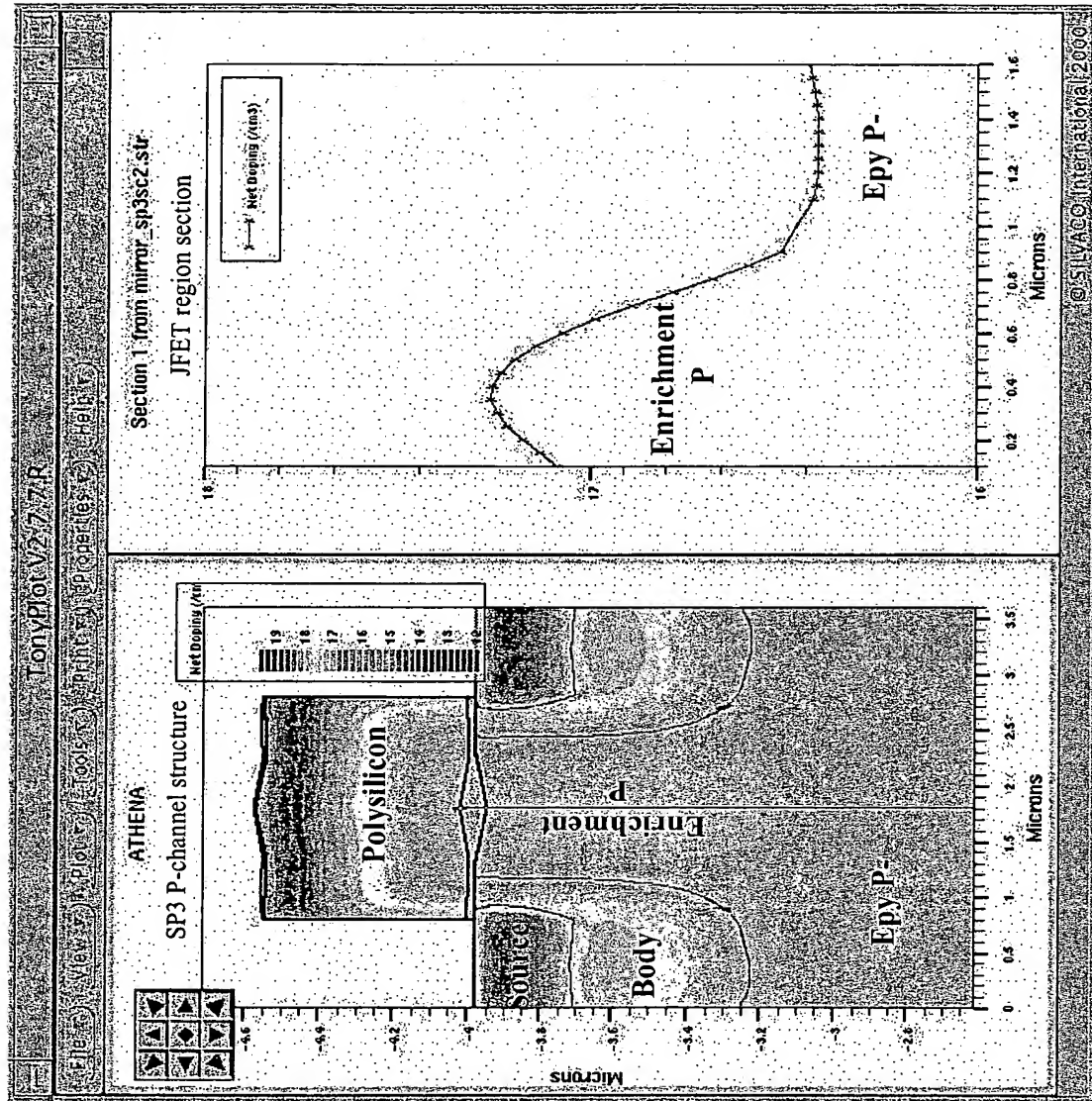


FIG. 8